

Amendments to the Claims:

The listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1-7 (Canceled).

Please amend claims 8 and 11 as follows:

8. (Amended) A method, comprising:

forming a layer made of a first material over a substrate;

selectively removing portions of the layer to form regions separated by a spacing that is made of the first material; and

filling the regions with a second material different from the first material; and

removing excess portions of the second material formed over the first material and over the regions.

Claim 9 (Canceled).

Please cancel claim 10 without prejudice.

Claim 10 (Canceled).

11. (Amended) The method of claim [[10]]8 wherein removing the excess portions comprises using a chemical-mechanical polishing technique.

12. (Original) The method of claim 8, further comprising forming another layer over the regions and over the spacing.

13. (Original) The method of claim 8 wherein filling the regions comprises using a deposition or re-flow process to fill the regions with the second material.

14. (Original) The method of claim 8 wherein selectively removing portions of the layer includes:

lithographically patterning the regions and the spacing, wherein a width of the spacing is reduced relative to a width of the regions; and

vertically etching the layer based on the lithographic patterning to remove portions of the first material corresponding to the region.

15. (Original) The method of claim 14 wherein lithographically patterning the regions and the spacing includes using a mask.

Claims 16-21 (Canceled).